AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

In the claims

- 1-9. (Canceled)
- 10. (Currently amended) [[A]] <u>The</u> method of <u>claim 24</u> manufacturing a magnetic recording medium, comprising:

depositing a magnetic recording layer on a substrate,

depositing a caplayer on the magnetic recording layer and

annealing the caplayer *in situ* at a temperature of from about 150°C to about 550°C thereby manufacturing said magnetic recording medium, wherein the magnetic recording layer comprises CoCrPt.

- 11. (Canceled)
- 12. (Currently amended) The method of claim [[10]] <u>24</u>, further comprising depositing a protective layer on the caplayer after annealing.
- 13. (Currently amended) The method of claim [[10]] <u>24</u>, wherein annealing is carried out at from about 250°C to about 350°C.
- 14. (Currently amended) The method of claim [[10]] <u>24</u>, wherein the annealing is carried out for less than about 30 seconds.
- 15. (Currently amended) The method of claim [[10]] <u>24</u>, wherein the annealing is carried out for about 14 seconds at a temperature of about 300°C.

- 16. (Currently amended) The method of claim [[15]] <u>24</u>, wherein the caplayer has a thickness of from about 0.5 nm to about 5 nm.
- 17. (Currently amended) The method of claim [[10]] <u>24</u>, wherein prior to depositing the caplayer on the substrate, the process further comprises:

depositing a sub-seed layer on the substrate;
depositing a seed layer on the substrate;
depositing an underlayer on the seed layer and
depositing a intermediate layer on the underlayer;
wherein the magnetic layer is deposited on the intermediate layer.

- 18. (Original) The method of claim 17, wherein the magnetic layer comprises at least one of Co, Cr, B, Pt, Ta, and Nb.
- 19. (Original) The method of claim 18, wherein the magnetic layer comprises a layer of CoCrPt having a thickness of from about 100 nm to about 400 nm.
 - 20. (Canceled)
- 21. (Currently amended) [[A]] <u>The</u> method of <u>claim 24</u> manufacturing a magnetic recording medium, comprising:

depositing a magnetic recording layer on a substrate,
depositing a caplayer on the magnetic recording layer and

annealing the caplayer *in situ* at a temperature of from about 150°C to about 550°C thereby manufacturing said magnetic recording medium, wherein the magnetic recording layer comprises Co and Cr.

22. (Canceled)

23. (Currently amended) The method of claim 22 A method of manufacturing a magnetic recording medium, comprising:

depositing a magnetic recording layer on a substrate,

depositing a caplayer on the magnetic recording layer and

annealing the caplayer in situ at a temperature of from about 150°C to about 550°C

thereby manufacturing said magnetic recording medium, wherein the caplayer comprises Cr and wherein the caplayer further comprises Mn.

24. (Currently amended) The method of claim 23 A method of manufacturing a magnetic recording medium, comprising:

depositing a magnetic recording layer on a substrate,

depositing a caplayer on the magnetic recording layer and

annealing the caplayer in situ at a temperature of from about 150°C to about 550°C

thereby manufacturing said magnetic recording medium, wherein the caplayer comprises Cr,

wherein the Cr content is less than 15 atomic percent.

- 25. (New) The method of claim 23, wherein the magnetic recording layer comprises Co and Cr.
- 26. (New) The method of claim 23, wherein the magnetic recording layer comprises CoCrPt.
- 27. (New) The method of claim 23, further comprising depositing a protective layer on the caplayer after annealing.
- 28. (New) The method of claim 23, wherein annealing is carried out at from about 250°C to about 350°C.

- 29. (New) The method of claim 23, wherein the annealing is carried out for less than about 30 seconds.
- 30. (New) The method of claim 23, wherein the annealing is carried out for about 14 seconds at a temperature of about 300°C.
- 31. (New) The method of claim 23, wherein the caplayer has a thickness of from about 0.5 nm to about 5 nm.
- 32. (New) The method of claim 23, wherein prior to depositing the caplayer on the substrate, the process further comprises:

depositing a sub-seed layer on the substrate;
depositing a seed layer on the substrate;
depositing an underlayer on the seed layer and
depositing a intermediate layer on the underlayer;
wherein the magnetic layer is deposited on the intermediate layer.